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B.TECH. DEGREE EXAMINATION, NOVEMBER 2014

Third Semester

Branch—Electronics and Communication/Applied Electronics and Instrumentation/ Electronics and Instrumentation Engineering

SOLID STATE DEVICES (L A S)

(Prior to 2010 Admissions—Old Scheme)

[Supplementary/Mercy Chance]

Time: Three Hours

Maximum: 100 Marks

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Part A

Answer all questions briefly. Each question carries 4 marks.

- 1. Distinguish between direct and indirect bandgap semiconductors? Give examples.
- 2. Explain the conduction process by holes.
- 3. List and briefly explain the properties of depletion region of a *pn* junction.
- 4. What are the differences between Zener and Avalanche breakdown?
- 5. What is a varactor diode? What are its applications?
- 6. Draw the VI characteristics of a tunnel diode and label it.
- 7. Explain the doping profile in BJT and what is its significance.
- 8. What is Schottky transistor? What are its applications?
- 9. Define:
 - (i) pinch-off voltage;
- (ii) threshold voltage;
- (iii) saturation voltage; and
- (iv) breakdown voltage of a JFET.
- 10. What are the precautions to be taken while handling MOSFET? Why?

 $(10 \times 4 = 40 \text{ marks})$

Part B

Answer all questions.
Each full question carries 12 marks.

11. In a semiconductor at room temperature of 27°C, the intrinsic carrier concentration and resistivity are 1.5×10^{16} /m³ and 2×10^3 Ω m respectively. It is converted to an extrinsic semiconductor with a doping concentration of 10^{20} m³. For extrinsic semiconductor calculate:

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- (a) Minority carrier concentration;
- (b) resistivity;
- (c) shift in Fermi-level due to doping; and
- (d) Minority carrier concentration when its temperature is raised to a value at which intrinsic carrier concentration doubles. Assume $\mu_n = \mu_p = 2000 \text{ cm}^2/\text{Vs}$, kT = 26 mV at room temperature.

Or

- 12. (a) Derive the expression for the minimum conductivity of a semiconductor.
 - (b) Explain the transient decay of excess carriers in a semiconductor with direct recombination. Explain minority carrier life time.
- 13. In a p^+nn^+ junction diode, made of silicon the doping concentration of n-region is 5×10^{15} /cc. If the circuit field at avalanche breakdown is 3×10^5 V/cm, find :
 - (a) the breakdown voltage if the width of n-region is (i) 10 μm ; (ii) 5 μm ; (iii) 1 μm .
 - (b) Sketch and label the electric field distribution.

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- 14. Sketch the profiles and derive expressions for:
 - (i) build-in potential;
 - (ii) electric field distribution;
 - (iii) depletion layer capacitance of a linearly graded *p-n* junction.
- 15. (a) Derive expression for the time variation of voltage across a *p-n* junction as it is switched from forward-bias to reverse-bias condition.

(8 marks)

(b) Draw the characteristics of a tunnel diode and explain.

(4 marks)

Or

- 16. (a) Derive the expression for conductance of a diode. How does it vary with variation in forward-bias?
 - (b) What is Zener diode and how does it regulate the voltage?
- 17. Plot the minority carrier distribution in a p-n-p BJT in all the three regions and label it properly for (i) active region; (ii) cut-off region; and (iii) saturation region.

Or

18. Draw the n-p-n and p-n-p transistors. Label all the currents when biased in active region and show the direction of carrier flow in both types of transistors? Derive expressions for the current components.



- 19. A silicon MOS system with p-type substrate with $N_A = 10^{15}$ /cc, oxide thickness = 100 Å; at the onset of strong inversion. Determine :
 - (a) width of depletion layer;
 - (b) the charge density in the depletion layer;
 - (c) the electron density n_s at the surface; and
 - (d) the threshold voltage. Assume $\epsilon_{rox} = 3.9, \ n_i = 1.5 \times 10^{10}/\text{cc}$.

Or

20. Derive expression for the drain current of JFET. What are the approximations made? Explain the effect of increase in temperature on the drain current.

 $(5 \times 12 = 60 \text{ marks})$